

# Determining Thermal Equilibrium Defect Densities for Transition Metal Dichalcogenides from First Principles and Experimental Thermodynamics

Luke N. Holtzman<sup>1</sup>, Preston A. Vargas<sup>2</sup>, Song Liu<sup>3</sup>, James Hone<sup>3</sup>, Richard G. Hennig<sup>2</sup>, Katayun Barmak<sup>1</sup>

<sup>1</sup>Department of Applied Physics and Applied Mathematics, Columbia University, New York, NY 10027

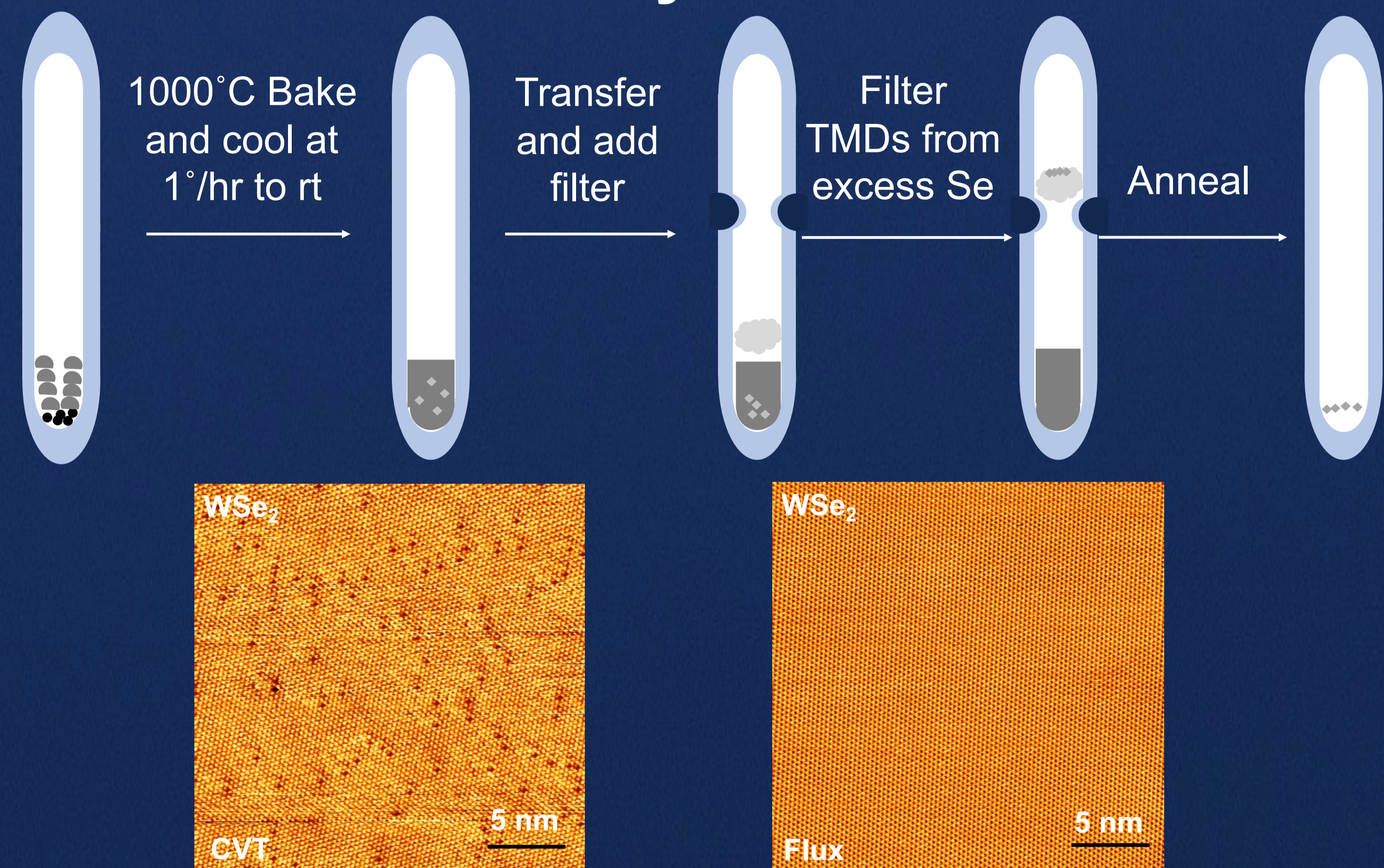
<sup>2</sup>Department of Materials Science & Engineering, University of Florida, Gainesville, FL 32611

<sup>3</sup>Department of Mechanical Engineering, Columbia University, New York NY 10027

## Abstract

Two-dimensional transition metal dichalcogenides (TMDs) have gained interest due to their novel optical and electronic phenomena and potential for optoelectronic applications. Chemical vapor deposition (CVD) and chemical vapor transport (CVT) are commonly used to synthesize TMDs due to their fast growths and high yields; however, they produce highly defective TMDs, negatively impacting the novel properties. Alternatively, the self-flux growth method has been shown to yield TMDs with defect densities several orders of magnitude lower than those from CVD and CVT. Yet, it is unknown how close the self-flux TMDs quality is to the thermal equilibrium defect density. In this work, we perform density functional theory calculations for intrinsic defects and substitutional oxygen impurities in WSe<sub>2</sub>. We use ab initio modeling in conjunction with experimental thermodynamic data to calculate equilibrium formation energies and defect densities as a function of growth temperature. Theoretical chalcogen point defect densities at the self-flux growth conditions were shown to be an order of magnitude less than experimental values. The defect density difference between experiment and theory suggests that equilibrium was not reached, and kinetic or impurity factors alter the self-flux TMDs defect densities.

## Flux Synthesis



## Introduction

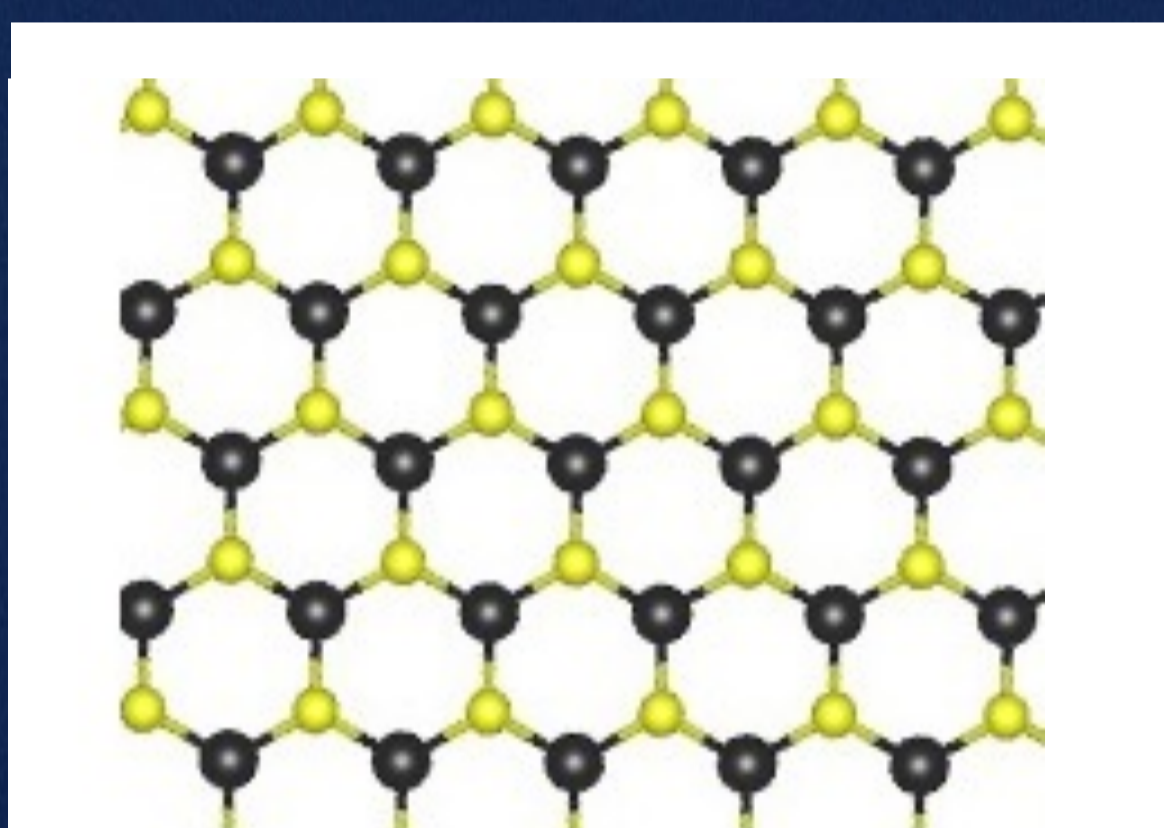
### Layered Materials

- Weak van der Waals forces
- Exfoliate to monolayer

### Point Defects

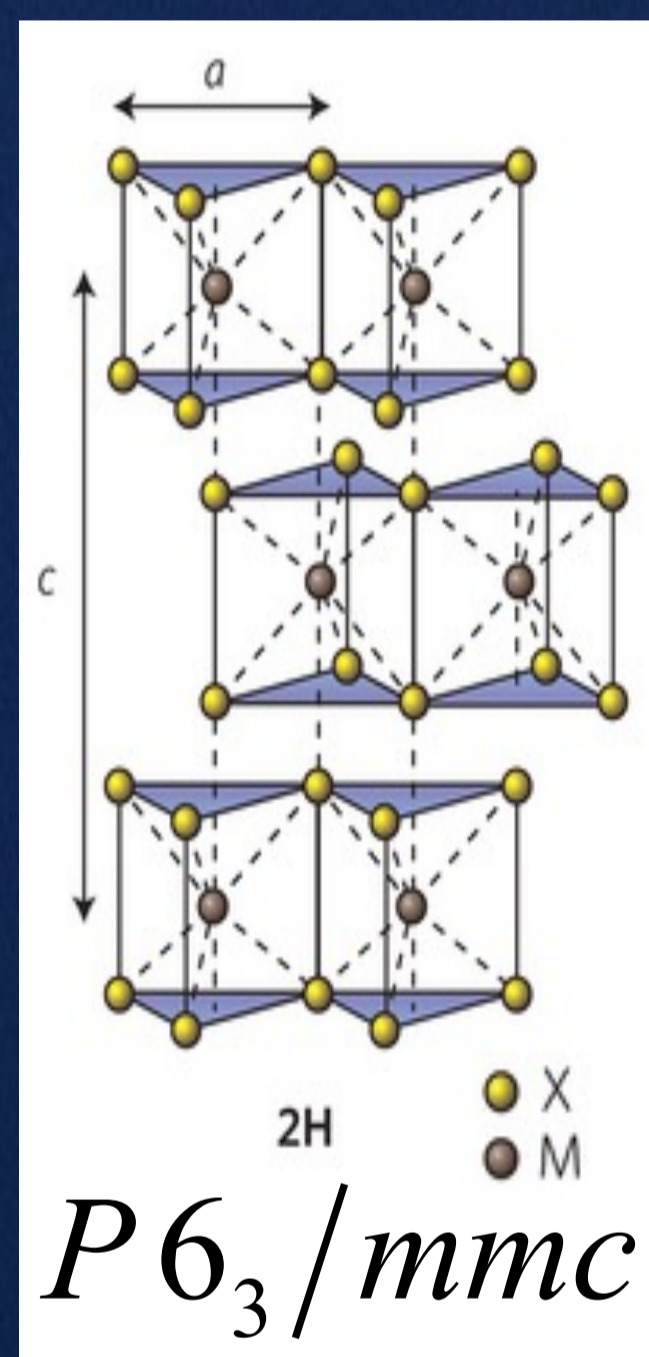
- Intrinsic
- Vacancies
- Interstitials
- Antisites

### Top down view of monolayer



$\bar{p}6m2$

### 2H-Phase



$P6_3/mmc$

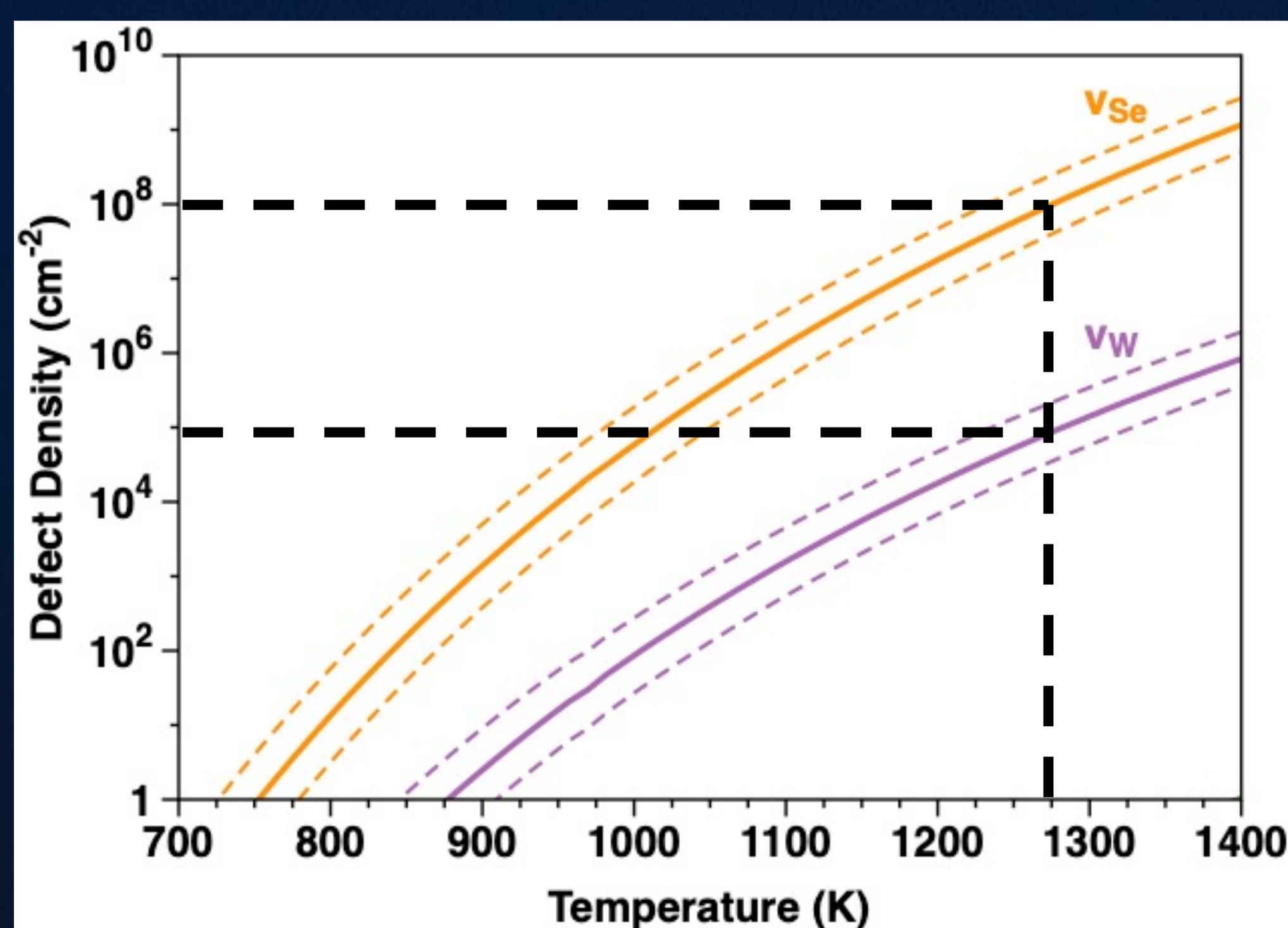
## Thermodynamic Intrinsic Defect Density Limit

- Arrhenius relationship

$$c = N_0 N_C \exp\left(-\frac{G_f(T)}{k_B T}\right)$$

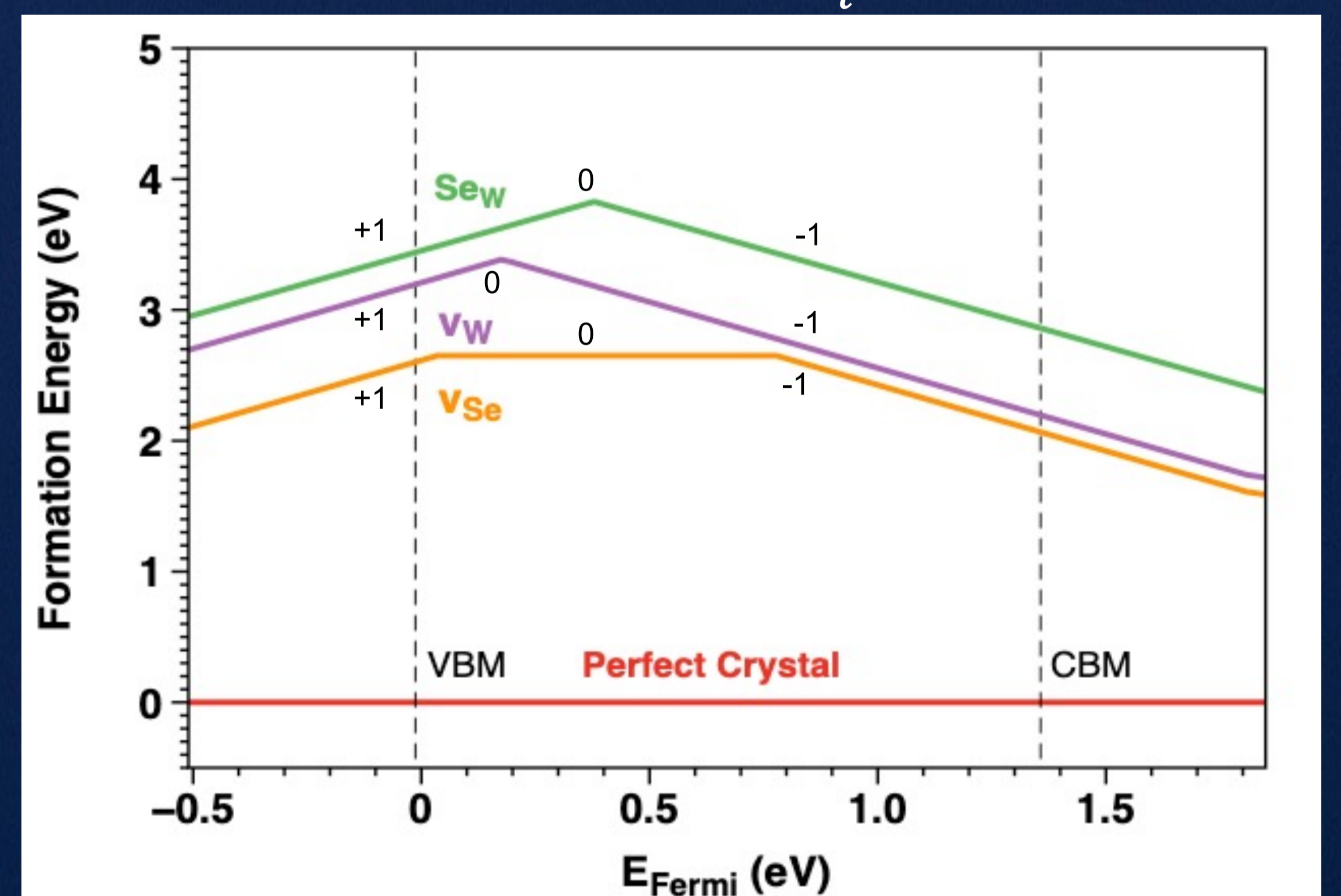
- $N_0$  = Areal density of WSe<sub>2</sub> unit cells
- $N_C$  = # of inequivalent sites per unit cell

At 1273 K	Calculated (cm <sup>-2</sup> )	Experimental (cm <sup>-2</sup> )
Se vacancies	$9.4 \cdot 10^7$	$10^{10} - 10^{11}$
W vacancies	$8.3 \cdot 10^4$	$10^9 - 10^{10}$

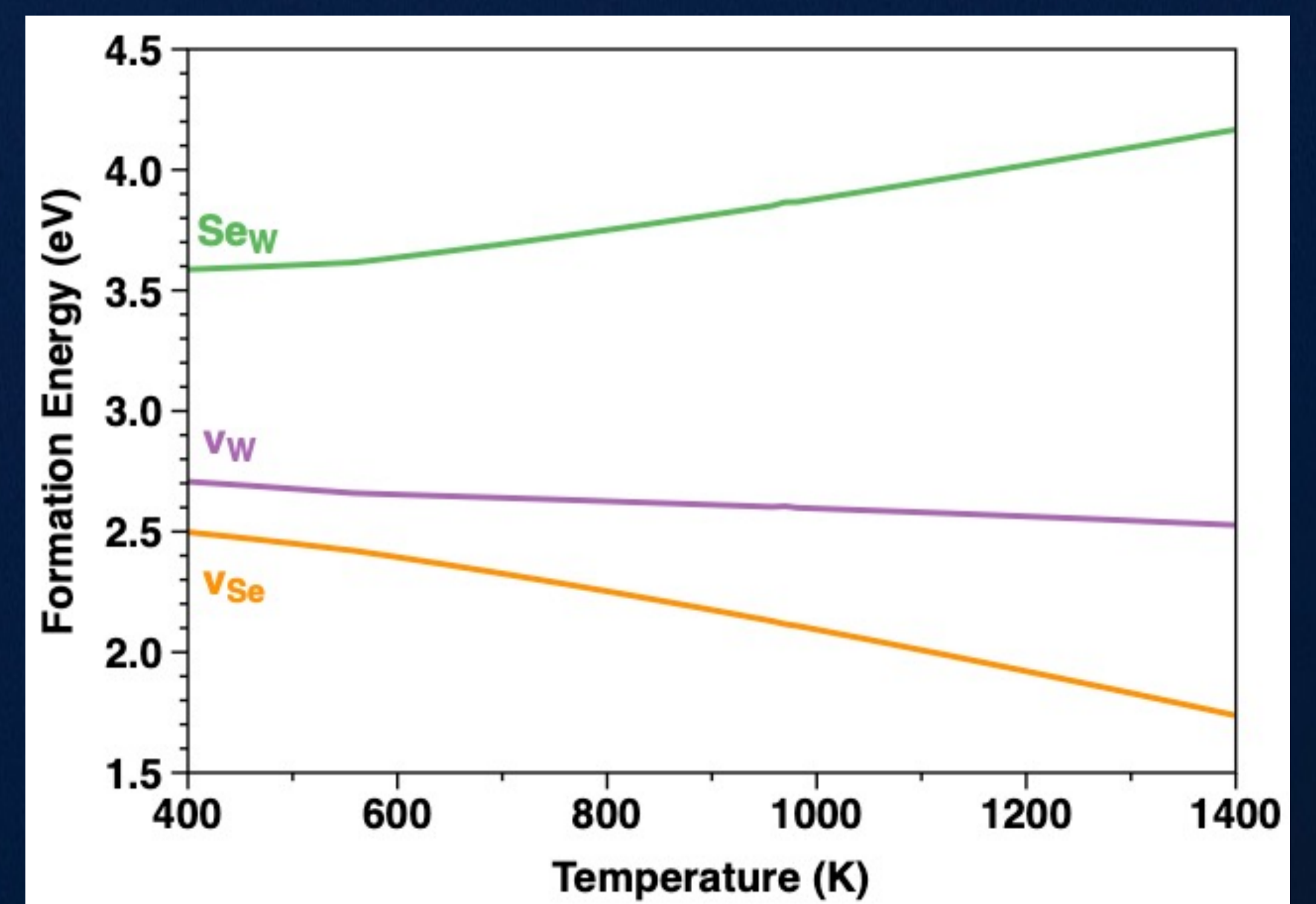


## Defect Formation Energies

$$E_{D,q}^{form}(E_F, \mu) = [E_{D,q} - E_{pc}] - \sum_i n_i \mu_i + q E_F + E_{corr}$$



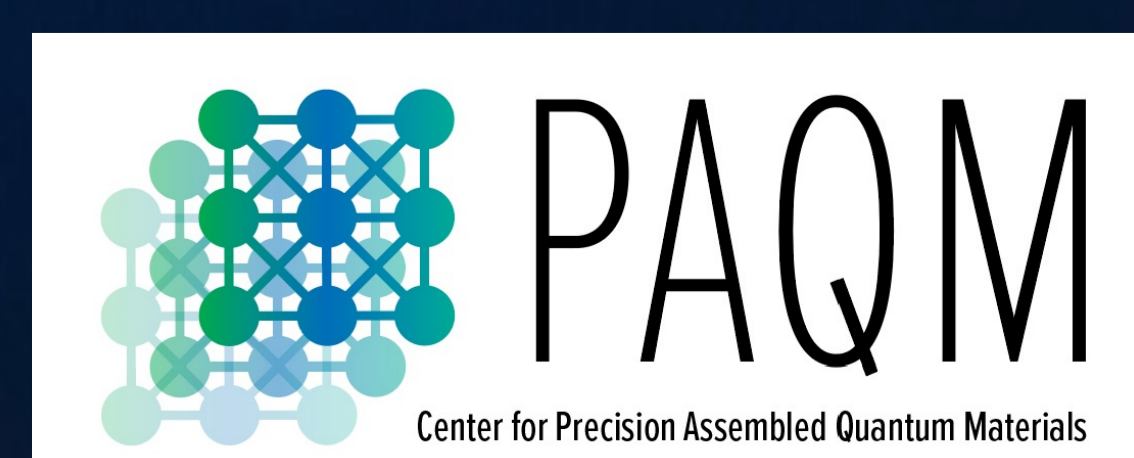
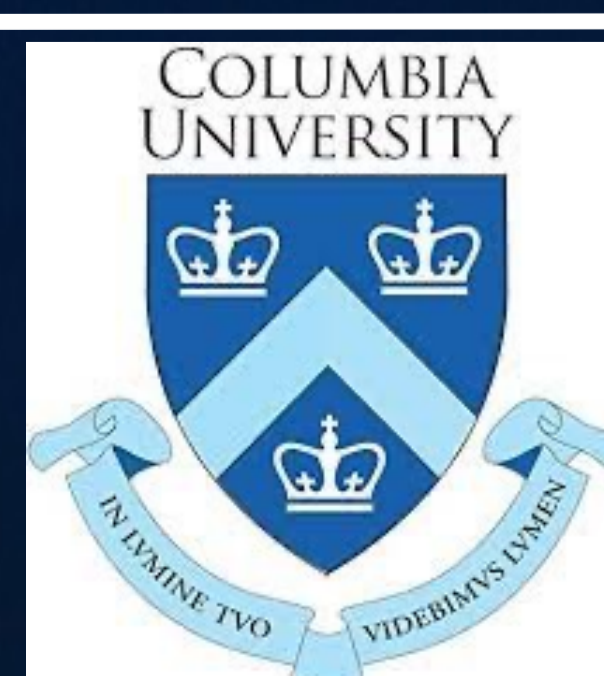
Bulk Intrinsic Defect Formation Energies at 0 K



Temperature-Dependent Bulk Intrinsic Defect Formation Energies

## References

Wang, et al., Nat. Nanotechnol. 6, 699 (2012)  
Edelberg, D. et al. Nano Letters 19, 4371-4379, (2019)



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